

## Special Issue

# Advances in Semiconductor Photocatalysis

### Message from the Guest Editors

Semiconductor materials have long been used as photocatalysts for various applications. In recent years, many methods have been developed in order to improve the photocatalytic activity of traditional semiconductor materials such as TiO<sub>2</sub>. Besides the “old materials”, novel semiconductor materials have been explored for photocatalysis applications, and significant advances have been made. New concepts, like “plasmonic photocatalysis” and “photonic photocatalysis” have been devised. The new materials and new methods can significantly enhance photocatalysis efficiency and overcome many drawbacks associated with the traditional semiconductor photocatalysts. This Special Issue aims to provide a platform for scientists and engineers to report the most exciting advances made in this field. We would like to invite colleagues to contribute to this Special Issue. We expect to see amazing studies on semiconductor photocatalysts synthesis, novel methods for photocatalysis enhancement, and novel applications of semiconductor photocatalysts in any form of photocatalytic processes.

Prof. Dr. Jia Hong Pan

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### Guest Editors

Prof. Dr. Zhongyu Cai

School of Instrumentation and Optoelectronic Engineering, Beihang University, Beijing 100191, China

Prof. Dr. Jiahong Pan

College of Environmental Science and Engineering, North China Electric Power University, Beijing 102206, China

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### Deadline for manuscript submissions

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## Applied Sciences

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Editorial Office  
MDPI, Grosspeteranlage 5  
4052 Basel, Switzerland  
Tel: +41 61 683 77 34  
[appls@mdpi.com](mailto:appls@mdpi.com)

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### Editor-in-Chief

Prof. Dr. Giulio Nicola Cerullo  
Dipartimento di Fisica, Politecnico di Milano, Piazza L. da Vinci 32,  
20133 Milano, Italy

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